

Lab Project #1

Due Wednesday, 1/20/2016 by 5:00pm

This lab is designed to help you become familiar with photolithography. In this lab, using the mask provided by Bob Hill, you will expose and develop 3 different silicon samples using either 3 different developing times or 3 different exposure times (only change 1 of these, not both). One of the samples should be developed (or exposed) for the recommended amount of time, 1 should be overdeveloped (or overexposed, use at least 2x the recommended develop or expose time), and 1 should be underdeveloped (or underexposed). Take pictures of the 3 samples and compare them. You should turn in the pictures along with a write-up/analysis. This lab is to be completed in groups of 2.